



**THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the application of:

Teiichirou Chiba *et al.*

Serial No.: 09/492,761

Examiner: C. Chu

Filed: January 27, 2000

Group Art Unit: 2815

For: SEMICONDUCTOR WAFER

12-20-01

T. Flores  
REC'D 12/17/2001  
C 2800 MAIL ROOM

**RESPONSE UNDER 37 C.F.R. § 1.111**

Honorable Commissioner  
of Patents and Trademarks  
Washington, D.C. 20231

December 13, 2001

Dear Sir:

The following amendments and remarks are submitted in response to the Official Action mailed September 13, 2001. The Official Action set forth a three-month period for response, making this response to one or before December 13, 2001.

Please amend the above-identified application as follows:

**IN THE SPECIFICATION:**

Please replace the paragraph beginning at page 23, line 15, with the following rewritten paragraph:

*A 1* *Ansby* -- A plane shape of the notch 1 is as shown by Fig. 2. In plane view, a longest dimension from a side face of the wafer W to a bottom portion of the notch 1 falls in a range of 1 to 1.25 mm, the bottom portion defines a circular